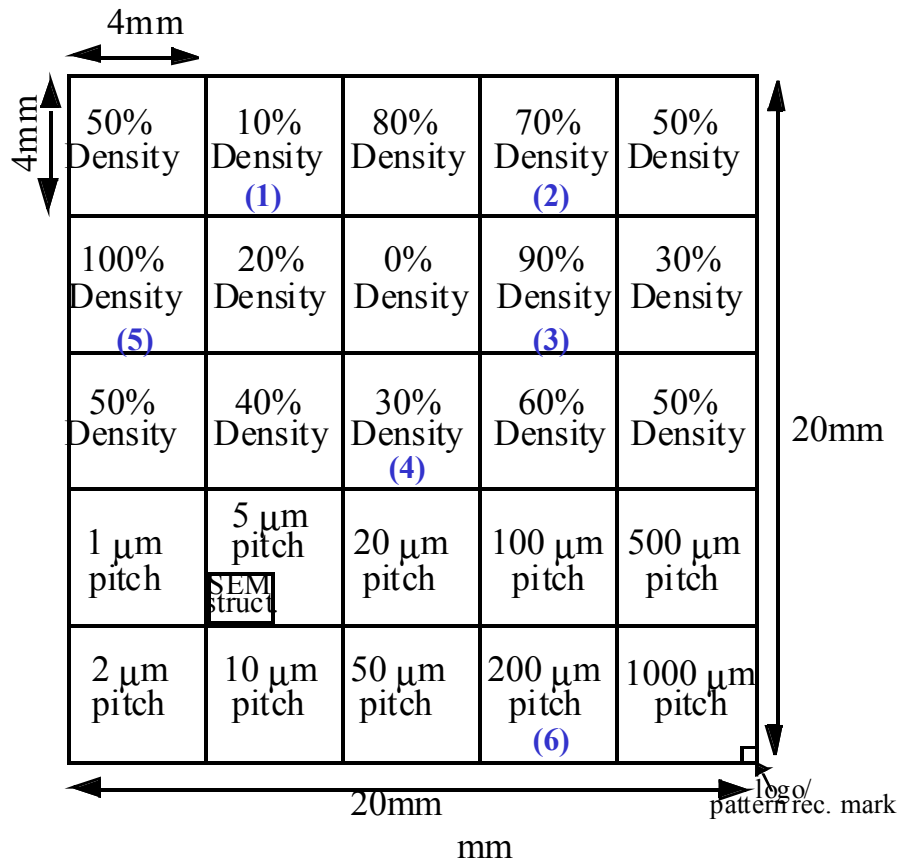
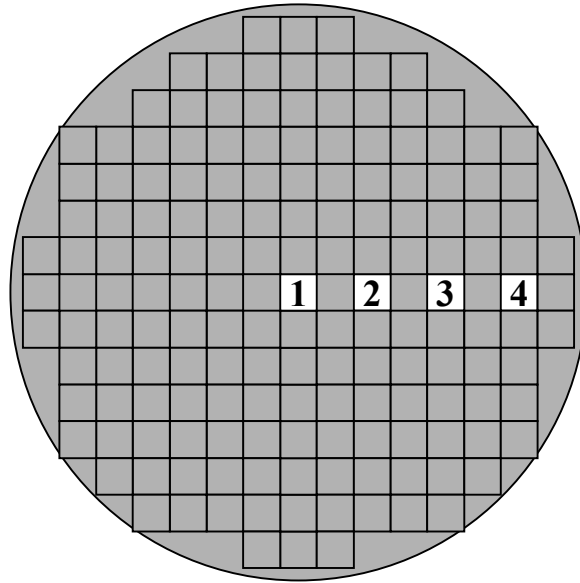


# Basic Oxide Thickness Measurement Plan

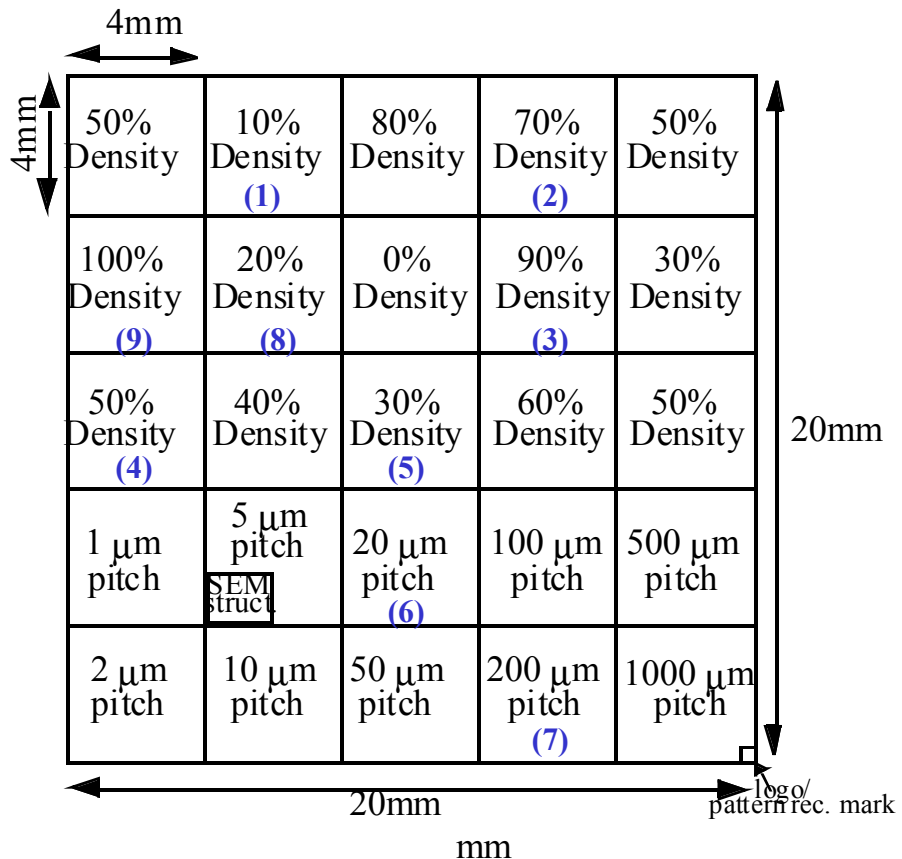
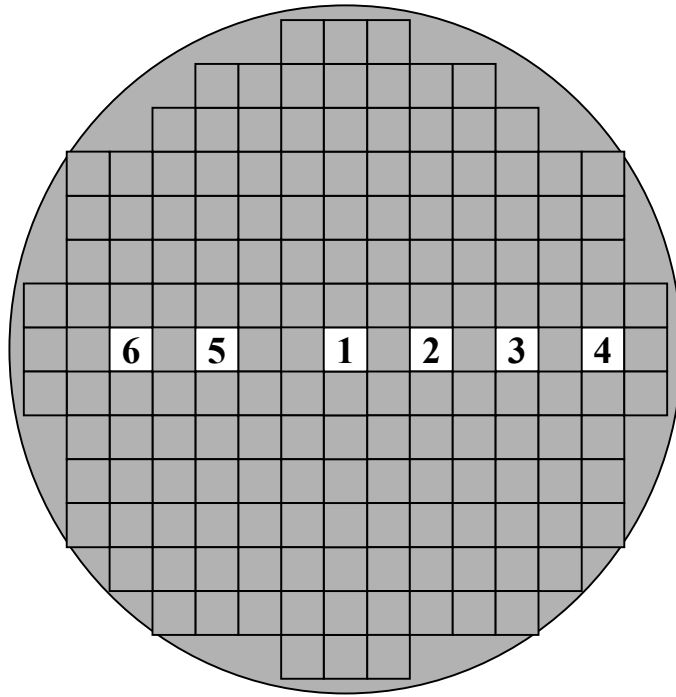
(Type: SKW 3-2, 300mm, 4 dies/wafer, 6 sites/die)



SKW3-2 Mask Floor Plan

# Standard Oxide Thickness Measurement Plan

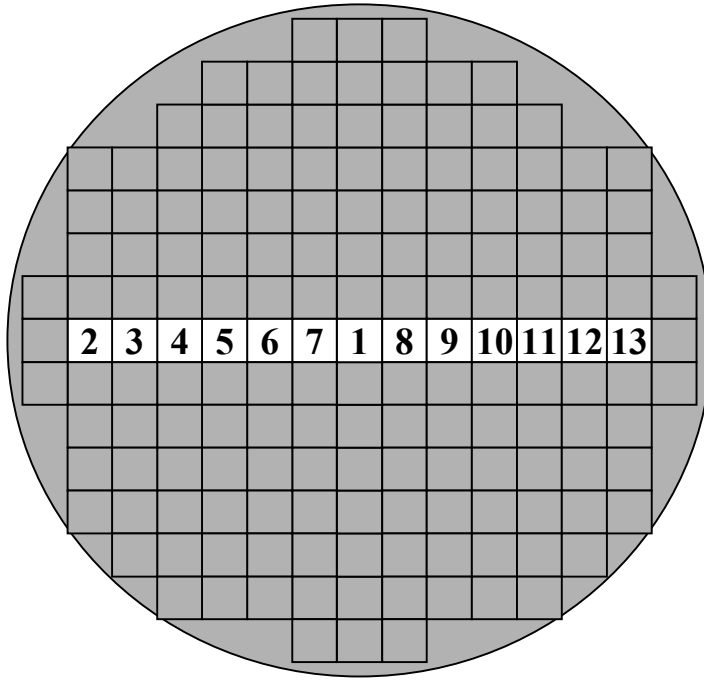
(Type: SKW 3-2, 300mm, 6 dies/wafer, 9 sites/die)



SKW3-2 Mask Floor Plan

# Advanced Oxide Thickness Measurement Plan

(Type: SKW 3-2, 300mm, 13 dies/wafer, 10 sites/die)



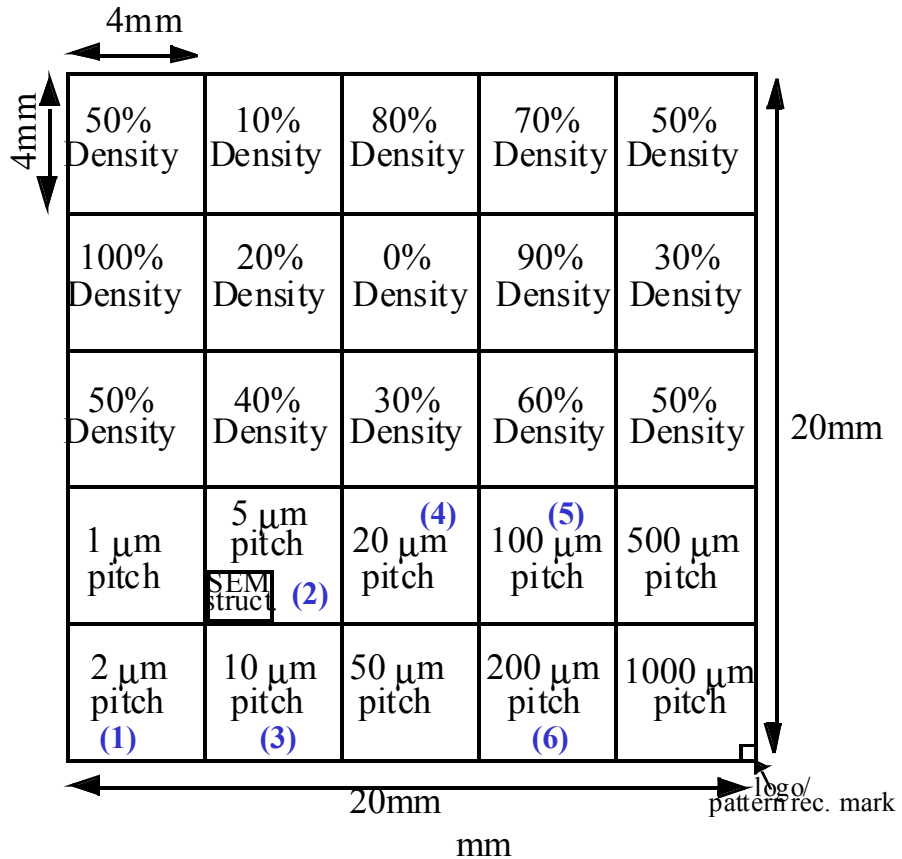
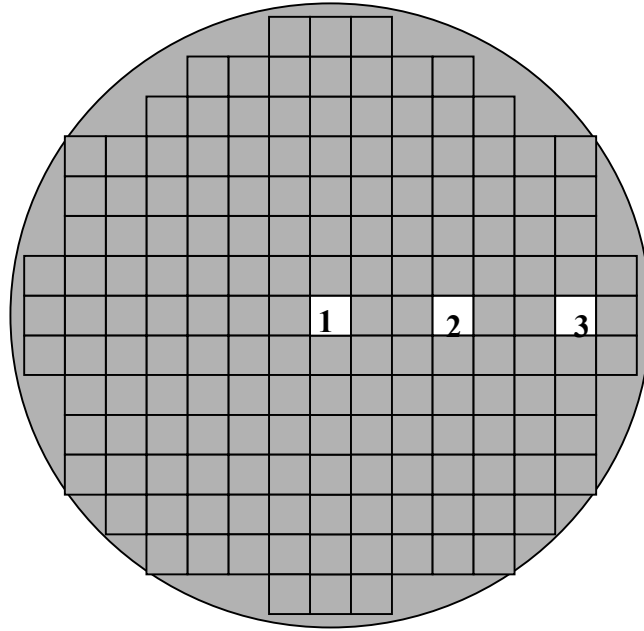
4mm	4mm						20mm
4mm	50% Density	10% Density (1)	80% Density	70% Density (2)	50% Density	20mm	
	100% Density (9)	20% Density (8)	0% Density	90% Density (3)	30% Density		
	50% Density (4)	40% Density (10)	30% Density (5)	60% Density	50% Density		
	1 μm pitch	5 μm pitch SEM struct	20 μm pitch (6)	100 μm pitch	500 μm pitch		
	2 μm pitch	10 μm pitch	50 μm pitch	200 μm pitch (7)	1000 μm pitch		
	20mm					logo/ pattern rec. mark	
	mm						

**SKW3-2 Mask Floor Plan**



# Standard Step Height Measurement Plan (II)

(Type: SKW 3-2, 300mm, 3 dies/wafer, 6 scans/die)



SKW3-2 Mask Floor Plan